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PATENT  
5/16/02

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of: O'DONNELL

Attorney Docket No.:  
LAM1P133/P0582

Application No.: 09/472,757

Examiner: UMEZ ERONINI, Lynette T.

Filed: December 27, 1999

Group: 1765

Title: INSITU POST ETCH PROCESS TO  
REMOVE REMAINING PHOTORESIST AND  
RESIDUAL SIDEWALL PASSIVATION

**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the  
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Signed: \_\_\_\_\_

Sue Funchess

**AMENDMENT B**

Box AF  
Commissioner for Patents  
Washington, D.C. 20231

Dear Madame:

RECEIVED  
MAY 15 2002  
TC 1700

This is in response to the office action mailed March 12, 2002. Please consider the following remarks and amend the above-identified patent application as follows:

**REMARKS**

Claims 1-18 are pending in the present application.

The applicant would like to thank the Examiner for her time during the telephone call of April 25, 2002.

The applicant requests reconsideration of the final rejection. Claims 1-16 were not amended. However, in the final rejection, the Examiner provided new grounds for rejection, by citing Brown et al.

The Examiner rejected claim 18 under 35 U.S.C. § 112, first paragraph, as containing subject matter which is not described in the specification in such a way as to reasonably convey to one skilled in the relevant art that the inventors at the time the application was filed had possession of the claimed invention. The Examiner stated lines 1-3, of claim 18, stating, "wherein the stripping away comprises accelerating oxygen plasma to the substrate to remove